AMENDMENTS TO THE ABSTRACT OF THE DISCLOSURE

Please amend the Abstract by rewriting same to read as follows.

In order to make it possible to simply transcribe a pattern without seams of a photomask onto the whole or part of a die having a three-dimensional shape, a general-purpose polyester film coated with a photosensitive material is used as a photomask 2 and, after forming a pattern, the photomask 2 is struck through vacuum molding or the like to a die 1' molded into the same shape as that of a die 1 to be exposed and developed.